

Docket No.: N9460.0016/P016  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Takashi Onishi, et al.

Application No.: Not Yet Assigned

Confirmation No.:

Filed: Concurrently Herewith

Art Unit: N/A

For: ELECTRON BEAM LITHOGRAPHY  
SYSTEM AND METHOD THEREFOR

Examiner: Not Yet Assigned

**CLAIM FOR PRIORITY**

MS Patent Application  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Applicant hereby claims priority under 35 U.S.C. 119 based on the following prior foreign application filed in the following foreign country on the date indicated:

<u>Country</u>	<u>Application No.</u>	<u>Date</u>
Japan	2002-289879	October 2, 2002

Application No.: Not Yet Assigned

Docket No.: N9460.0016/P016

In support of this claim, a certified copy of the said original foreign application will be filed shortly.

Dated: October 1, 2003

Respectfully submitted,

By 

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